希爱®

长春新产业光电技术有限公司

Changchun New Industries Optoelectronics Tech. Co.,Ltd.

DATA SHEET

NS-FH-532/1-30W

PICOSECOND PULSED LASER AT 532nm

Nanosecond pulsed laser at 532nm is made features of short pulse duration, high repetition rate, high stability and good beam quality, which is used in sapphire marking, ceramic cutting, semiconductor cutting, film scribing, physics experiment, etc.

SPECIFICATIONS

Wavelength (nm)	532±1
Operating mode	Pulsed
Average power (W)[1]	1-30
Single pulse energy (uJ)	100μJ@200kHz；30μJ@1MHz；20μJ@1.5MHz
Rep. rate [2]	0.2-10MHz
Pulse duration (ns) [3]	2-10@1.5MHz
Peak power (MW)	1-20
Ave power stability (rms, 4 hours±3°C)	<2%, <1%
Warm-up time (minutes)	<10
Transverse mode	TEM_{00}
M^2	<1.3
Beam divergence, full angle (mrad)	<1
Beam diameter at the aperture ($1/e^2$,mm)	<3
Polarization ratio	>100:1 Horizontal
Beam height from base plate (mm)	114
Cooled method	Water cooled
Operating temperature (°C)	10-35
Power supply (100-240VAC)	RAD1PS
Expected lifetime (hours)	>10000

AVOID EXPOSURE-LASER RADIATION IS EMITTED FROM THIS APERTURE

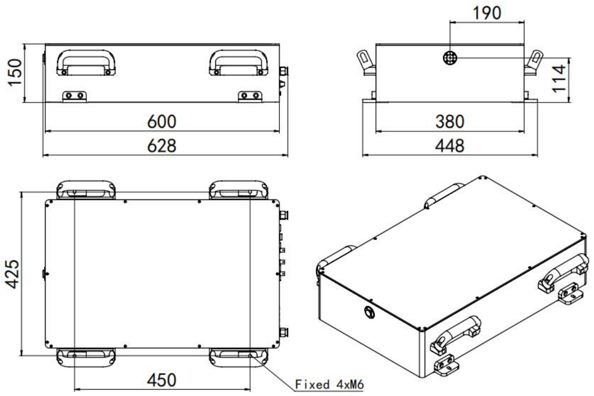
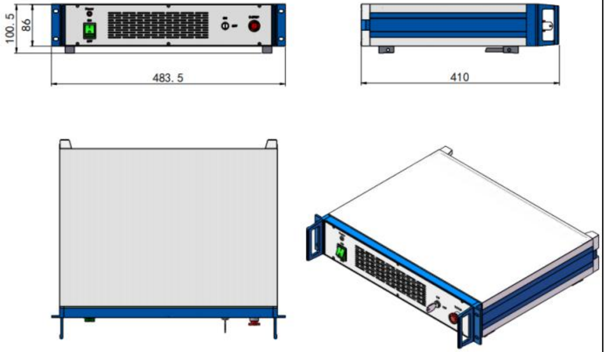
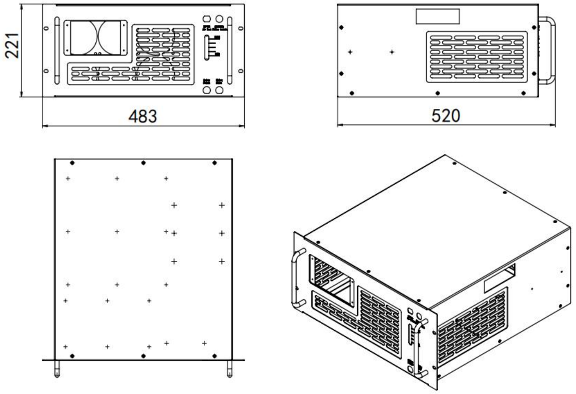
DANGER

VISIBLE AND INVISIBLE LASER RADIATION – AVOID EYE
OR SKIN EXPOSURE TO DIRECT OR SCATTERED RADIATION

Maximum Output: 5mJ Wavelength: 400-700nm
Pulse Duration: <500ns

CLASS IV LASER PRODUCT

This device complies with 21 CFR 1010 and 1040
Changchun New Industries Optoelectronics Tech. Co., Ltd.
No. 888 Jinhu Road, High-tech Zone, Changchun, China

LASER HEAD (DRIVER Integrated)	POWER SUPPLY	WATER CHILLER
 	 	
628 (L)×448 (W) ×150 (H) mm^3,55kg	**410 (L) ×483.5 (W) ×110.5 (H) mm^3,4.5 kg**	**520 (L) ×483 (W) ×221 (H) mm^3,22kg**

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1 One fixed value between 1-30W.

2 Rep.rate range available on request.

3 Pulse width range available on request.

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